

METHOD OF STABILIZING OXIDE ETCH AND CHAMBER PERFORMANCE USING SEASONING

Abstract of the Disclosure

Undesirable reactions (such as formation of volatile compounds or complexes) are recognized to occur during production processes (such as etching with fluorine) at interior surfaces of a reactor chamber (such as a silicon-based reactor chamber). These undesirable reactions may be minimized and controlled by priming the chamber surface by incorporating seasoning atoms and/or molecules.

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Figures

FIGURE 1